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Abstract

The carbon nanofilms on diamond were obtained by irreversible graphitization of diamond at above 1000 °C. The exposure to plasma reduces the surface conductance of the carbon nanofilms on diamond as result of a partial removal of carbon and the plasma-stimulated amorphization. The experimentally observed exponential dependence of conductance G of the carbon nanofilms on temperature T can be well represented by a relation $G = A \exp(BT)$. This behavior is explained by a model based on the thermally vibrating energy barriers formed between the carbon nanoclusters constituting the thin carbon nanofilms. The empirical constants A and B relate to the density of the carbon nanoclusters and the energy barrier height between them respectively. A rudimentary temperature and chemical sensor is demonstrated utilizing the electronic properties of resultant carbon system.

Introduction

Forms of Carbon

Crystalline, Amorphous & Glassy Carbon

Parameters of Graphitization

FIG. 1. Volume percentage of graphite produced from diamonds as a function of time at 2 GPa, for 30 min at different temperatures.
 FIG. 2. Volume percentage of graphite as a function of pressure at different annealing times.
 FIG. 3. Volume percentage of graphite produced from diamonds as a function of time at 2 GPa, for 30 min at different temperatures.
 FIG. 4. Volume percentage of graphite as a function of pressure at different annealing times.

Phase Diagram of Carbon

Diamond is a metastable form of diamond and converts into graphite at high temperatures

Thin Films of Carbon

Type: Graphite Like (GLC), Diamond Like (DLG)

Properties:

- Mixture of crystalline phases and amorphous phases
- Different ratios of sp^2 and sp^3
- Properties vary. Depends upon method of synthesis
- Diamond like or graphite like properties

Synthesis:

- Vapor Deposition
- Carbonization of Polymers
- Fast Ion Beam Lithography
- Thermal Treatment of Diamond
- Synthetic Methods for Graphene: Mechanical & Chemical

Why Diamond??

Nanoelectronic Application

- Excellent Substrate
- Diamond \leftrightarrow Graphite

- Very Good Insulator
- Excellent thermal conductor
- One of the hardest material
- Thermally stable
- Chemically inert
- Availability of synthetic diamonds
- As insulating substrate in electronic devices
- Employability in harsh conditions
- All-carbon technology
- Lab-on-chip

Instruments

Fabrication Scheme: Carbon Nano Layer

Graphitization of Diamond: Carbon Nanolayer

Measured Specific Resistances:
 HV film: $\sim 2.5 \times 10^5 \Omega \cdot m$
 LV film: $\sim 1.0 \times 10^6 \Omega \cdot m$

Types of Carbon	Specific Resistance
Isotropic graphite*	$9.5 \times 10^6 \Omega \cdot m$
Extruded	$8.0 \times 10^6 \Omega \cdot m$
Graphite	$9.0 \times 10^6 \Omega \cdot m$
Glassy Carbon	$4.2 \times 10^5 \Omega \cdot m$

Source: Tokai Carbon Company limited

PC: Polycrystalline, CVD: Chemical Vapor Deposition
 HV: ($2 \times 10^{-5} - 5 \times 10^{-2}$ mbar), LV: ($2 \times 10^{-2} - 3 \times 10^{-2}$ mbar)

Reduction in thickness by plasma etching

Surface Modification /Residual Carbons (Nanoislands)??

PC/HV/1200°C/30 min/Plasma Power 4

Current-Voltage (I-V) characteristics

(a) Thick films grown in low vacuum at 1200°C for 30 min: as-grown and after 5 minute plasma etching in air plasma
 (b) Thick films grown in Ar atmosphere at 1000°C for 10 min: as grown and exposed to water vapor of different densities (different droplet sizes)

Raman Spectrum

The Raman spectra of a thin carbon film grown on a PC-CVD diamond by annealing at 1200°C for 15 min in high vacuum (5×10^{-5} mbar) and the films obtained by successive plasma etching of this original film.

Atomic Force Microscopy (AFM) profile (tapping mode) of Carbon nanofilm

Formation of step:
 1. Silver Masking
 2. Plasma Etching

SC-CVD1200°C/LV
 HV Film $\sim 8-10$ nm
 LV Film $\sim 90-100$ nm

In situ conductance measurement

CVD1, single crystal mech. cleaning

In situ conductance measurement: Changes on the surfaces

Temperature sensitivity

HV Film: Original Film (blue), Etched Films (red)

Chemical Sensitivity: Response to a water drop

Approach of a water drop in 0.5 mm steps

Carbon nanofilm
 Diamond Substrate

Chemical Sensitivity: Selectivity

- Positive response to water or humane breathing
- Negative response to chemical analytes like acetone

Conclusions

- The temperature and chemical sensitive - few carbon atoms thin films of carbon can be obtained by thermal annealing of diamond films at high temperatures (higher than 1000°C) combined with plasma etching.
- The grown films are amorphous in nature with short range graphitic domains.
- The thin film obtained in high vacuum (5×10^{-5} mbar) is about 12 nm thick; while a thick film obtained in relatively low vacuum (2×10^{-2} mbar) is about 95 nm.
- The thickness of the thick LV film can be easily reduced to few nm by prolonged plasma etching to give a thin temperature sensitive film.
- Characterization techniques like X-Ray photoelectron spectroscopy (XPS) and X-Ray diffraction measurements (XRD) may give more insight into the material structure of these nano films. Besides, the role of pressure, temperature and annealing time needs to be investigated in more detail.
- Thus, we have an all carbon based technology to grow nano films of carbon for nano temperature and chemical sensor application.

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Acknowledgements

We acknowledge Army Research Office for supporting this project. We also wish to thank Dr. Yaling Wang for his help with AFM measurements.